



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : Confirmation No. 7480
Katsumi OOMORI et al. : Docket No. 2002-0089
Serial No. 10/059,210 : Group Art Unit 1752
Filed January 31, 2002 : Examiner S. Lee

5/22

POSITIVE-WORKING CHEMICAL-
AMPLIFICATION PHOTORESIST COMPOSITION

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

AMENDMENT

Assistant Commissioner for Patents,
Washington, D.C.

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Sir:

In response to the Official Action dated January 22, 2003, please amend the present application as follows:

IN THE CLAIMS:

Please amend claims 3-5 as follows:

3. (Amended) The positive-working chemical-amplification photoresist composition as claimed in claim 2 in which the tertiary alkyl group is tert-butyl group.

4. (Amended) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the component (B) is an onium salt compound containing a nonafluorobutane sulfonate ion as the anion.

5. (Amended) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which each of the first and second copolymeric resins has a weight-average molecular weight in the range from 3000 to 30000.